



PTO/SB/08A (08-03)  
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Substitute for form 1449/PTO		<b>Complete if Known</b>	
		Application Number	10/828,579
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> (Use as many sheets as necessary)		Filing Date	April 20, 2004
		First Named Inventor	A. Smith
		Art Unit	2878
		Examiner Name	Not yet assigned
		Attorney Docket Number	38203-6294
Sheet	1	of	5

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)			
WMA ↓	A	US- 4,861,148	08/29/1989	Sato et al.	
	B	US- 5,285,236	02/08/2004	Jain	
	C	US- 5,808,814	09/15/1998	Kudo	
	D	US- 6,142,641	11/07/2000	Cohen et al.	
	E	US- 6,356,345	03/12/2002	McArthur et al.	
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FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages Or Relevant Figures Appear	T <sup>6</sup>
		Country Code <sup>3</sup> Number <sup>4</sup> Kind Code <sup>5</sup> (if known)				

Examiner Signature	<i>Vincent Nelson</i>	Date Considered	25 Oct 05
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Application Number	10/828,579
Filing Date	April 20, 2004
First Named Inventor	A. Smith
Art Unit	2878
Examiner Name	Not yet assigned
Attorney Docket Number	38203-6294

Sheet 2 of 5

**NON PATENT LITERATURE DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
Wu	F	R. DeJule, "Mix-and-Match: A Necessary Choice", Semiconductor International, February 2000, pp. 66-76.	
	G	D G. Flagello et al., "Understanding Systematic and Random CD Variations Using Predictive Modelling Techniques", Proc. SPIE Vol. 3679, March 1999, pp. 162-175.	
	H	D. Cote et al., "Micrascan™ III Performance of a Third Generation, Catadioptric Step and Scan Lithographic Tool", Proc. SPIE Vol. 3051, pp. 806-816.	
	I	J. Mulken et al., "ArF Step and Scan Exposure System for 0.15 μm and 0.13 μm Technology Node?", Proc. SPIE Vol. 3679, March 1999, pp. 506-521.	
	J	M. A. van den Brink et al., "New 0.54 Aperture i-Line Wafer Stepper with Field by Field Leveling Combined with Global Alignment", Proc. SPIE Vol. 1463, 1991, pp. 709-724.	
	K	R. Rogoff et al., "Photolithography Using the Aerial™ Illuminator in a Variable NA Wafer Stepper", 1996, pp. 1-17.	
	L	J. Mulken et al., "High Throughput Wafer Steppers with Automatically Adjustable Conventional and Annular Illumination Modes", pp. 1-14.	
	M	L. Liebmann et al., "Understanding Across Chip Line Width Variation: The First Step Toward Optical Proximity Correction", Proc. SPIE Vol. 3051, 1997, pp. 124-136.	
↓	N	J. van Schoot et al., "0.7 NA DUV Step & Scan System for 150nm Imaging with Improved Overlay", Proc. SPIE Vol. 3679, 1999, pp. 448-456.	

Examiner Signature	<i>William Nelson</i>	Date Considered	26 Oct 05
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Application Number	10/828,579
Filing Date	April 20, 2004
First Named Inventor	A. Smith
Art Unit	2878
Examiner Name	Not yet assigned
Attorney Docket Number	38203-6294

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Wm	O	H.G. Müller et al., "Large Area Fine Line Patterning by Scanning Projection Lithography", MCM Proceedings, 1994, pp. 100-104.	
	P	J.E. Bjorkholm et al., "Reduction Imaging at 14 nm Using Multilayer-coated Optics: Printing of Features Smaller than 0.1 $\mu$ m", J. Vac. Sci. Technol. B8(6), pp. 1509-1513, 1990	
	Q	B.E. Newnam et al., "Development of XUV Projection Lithography at 60-80 nm", Proc. SPIE, Vol. 1671, 1992, pp. 419-436.	
	R	J. Kirk et al., "Pinholes and Pupil Fills", Microlithography World, Autumn 1997, pp. 25-28.	
	S	N. Farrar et al., "Illuminator Characterization Using In-Situ Reticle Diagnostic Structures".	
	T	N. Seong et al., "Differences of Pattern displacement Error Under Different Illumination Conditions", Proc. SPIE, Vol. 3334, 1998, pp. 868-872.	
	U	N. R. Farrar, "Effect of Off-Axis Illumination on Stepper Overlay", Proc. SPIE, Vol. 2439, 1995, pp. 273-275.	
	V	J. H. Bruning, "Optical Lithography - thirty Years and Three Orders of Magnitude", Proc. SPIE Vol. 3051, 1997, pp. 14-27.	
	W	D. G. Flagello et al., "Towards a Comprehensive Control of Full-Field Image Quality in Optical Photolithography", 1997, pp. 1-14.	
✓	X	J. Greeneich et al., "Advanced i-Line Illumination", Microlithography World, 1996, pp. 7-8.	

Examiner Signature	<i>Vincent Nelson</i>	Date Considered	26 Oct 05
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**INFORMATION DISCLOSURE  
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Application Number	10/705,597
Filing Date	November 10, 2003
First Named Inventor	A. Anandakumar
Art Unit	2133
Examiner Name	Not yet assigned
Attorney Docket Number	39908-6214

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Vmm	Y	D. W. Peters, "The Effects of an Incorrect Condenser Lens Setup on Reduction Lens Printing Capabilities", pp. 457-463.	
	Z	N. M. Ceglio et al., "Soft X-Ray Projection Lithography", J. Vac. Sci. Technol. B 8 (6), Nov/Dec 1990, pp. 1325-1328.	
	AA	Y. Borodovsky, "Impact of Local Partial Coherence Variations on Exposure Tool Performance", Proc. SPIE, Vol. 2440, pp. 750-770.	
	AB	H. Nomura et al., "Overlay Error Due to Lens Coma and Asymmetric Illumination Dependence on Pattern Feature", Proc. SPIE Vol. 3332, pp. 199-210.	
	AC	B. Katz et al., "High Numerical Aperture I-Line Stepper".	
	AD	D. S. Goodman et al., "Condenser Aberrations in Köhler Illumination", Proc. SPIE Vol. 922, 1988, pp. 108-134.	
	AE	C. Krautschik et al., "Mathematical Treatment of Condenser Aberrations and their Impact on Linewidth Control", Final Rev, March 23, 1999, pp. 1-12.	
	AF	International Technology Roadmap for Semiconductors, 2001 Edition, Front End Process", SEMATECH, pp. 1-44.	
	AG	International Technology Roadmap for Semiconductors, 2001 Edition, Executive Summary", SEMATECH, pp. 1-58.	
V	AH	International Technology Roadmap for Semiconductors, 2001 Edition, Lithography", SEMATECH, pp. 1-17.	

Examiner Signature	<i>V. N. Nelson</i>	Date Considered	26 Oct 05
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VHN	AI	International Technology Roadmap for Semiconductors, 2001 Edition, Metrology", SEMATECH, pp. 1-25.	
	AJ	International Technology Roadmap for Semiconductors, 2001 Edition, Modeling and Simulation", SEMATECH, pp. 1-16.	
	AK	International Technology Roadmap for Semiconductors, 2001 Edition, Yield Enhancement", SEMATECH, pp. 1-27.	
	AL	J. E. Bjorkholm, "EUV Lithography - the Successor to Optical Lithography?"; Intel Technology Journal, 1998, pp. 1-8.	
	AM	M. L. Freed, "Wafer-Mounted Sensor Arrays for Plasma Etch Processes", 2001, pp. 159.	
	AN	G. J. Swanson, "Binary Optics Technology: The Theory and Design of Multi-Level Diffractive Optical Elements", August 1989, pp. 47.	
	AO	W. Däschner et al., "General Aspheric Refractive Micro-Optics Fabricated by Optical Lithography Using a High Energy Beam Sensitive Glass Gray-Level Mask", J. Vac. Sci. Technol., B 14(6), Nov/Dec 1996, pp. 3730-3733.	
	AP	A.J. de Ruyter et al., "Examples of Illumination Source Effects on Imaging Performance", Arch Chemicals Microlithography Symposium, September 22, 2003, pp. 1-8.	
✓	AQ	Born et al., "Principles of Optics", 1959, pp. 524-526.	

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